

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	13496	STI or "shallow trench isolation"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/17 08:06
L2	763	"pad nitride" and trench and (mask\$3 or pattern\$3) and etch\$3	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/17 10:46
L3	303	1 and 2	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/17 08:09
L6	1	"6569750".PN.	USPAT; USOCR	OR	OFF	2005/05/17 08:24
L7	2152	(SiN or "silicon nitride") and ("silicon oxide" or SiO2) and trench and (mask\$3 or pattern\$3) and etch\$3 and pad	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/17 09:03
L8	776	7 and 1	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/17 09:03
L10	1	"6204172".PN.	USPAT; USOCR	OR	OFF	2005/05/17 09:41
L12	6	lee-sung-hoon.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/17 10:46
L13	801	"pad nitride" and (trench or groove) and (mask\$3 or pattern\$3) and (etch\$3 or remov\$3)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/17 10:47
L14	2	"6589879".pn.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/17 10:48